

# Lecture 2

## Semiconductor Physics (I)

### Outline

- Intrinsic bond model : *electrons and holes*
- Generation and recombination
- Intrinsic semiconductor
- Doping: *Extrinsic semiconductor*
- Charge Neutrality

#### **Reading Assignment:**

Howe and Sodini; Chapter 2, Sections 2.1-2.3

# Why are IC's made out of Silicon?

## **SILICON IS A SEMICONDUCTOR— a very special class of materials**

- Two types of “carriers” (mobile charged particles):
  - electrons and holes
- Carrier concentrations can be controlled over many orders of magnitude by addition “dopants”
  - selected foreign atoms
- Carrier concentrations can be controlled electrostatically
- ....

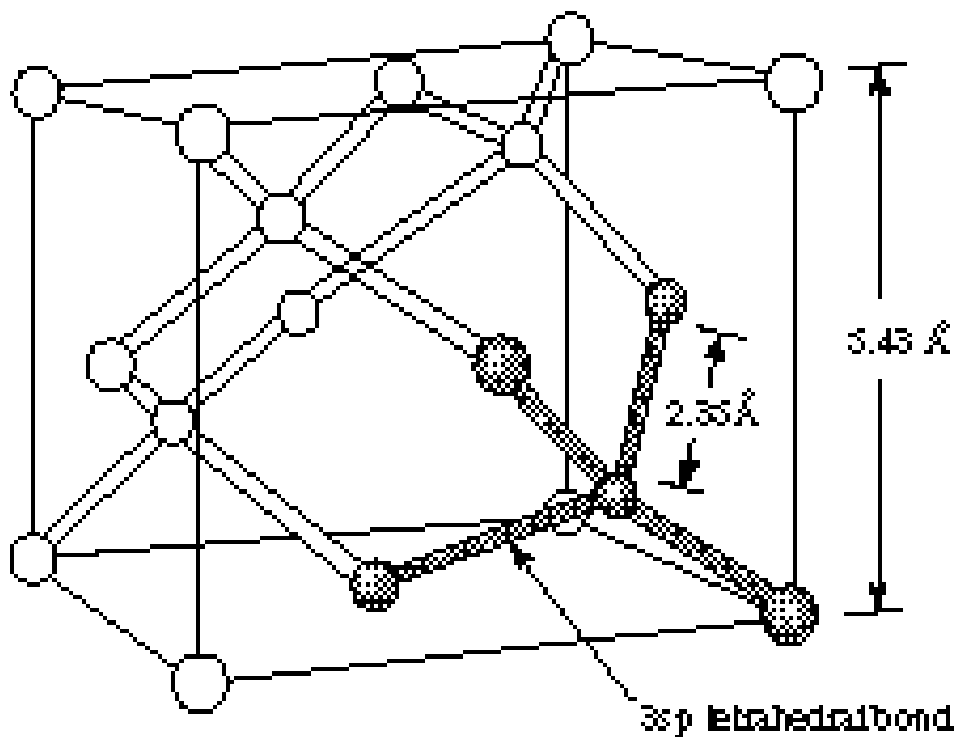
# 1. Silicon bond model: electrons and holes

Si is in Column IV of the periodic table:

	IIIA	IVA	VA	VIA
	5 B	6 C	7 N	8 O
	13 Al	14 Si	15 P	16 S
IIIB	30 Zn	31 Ga	32 Ge	33 As
	34 Se			
	48 Cd	49 In	50 Sn	51 Sb
				52 Te

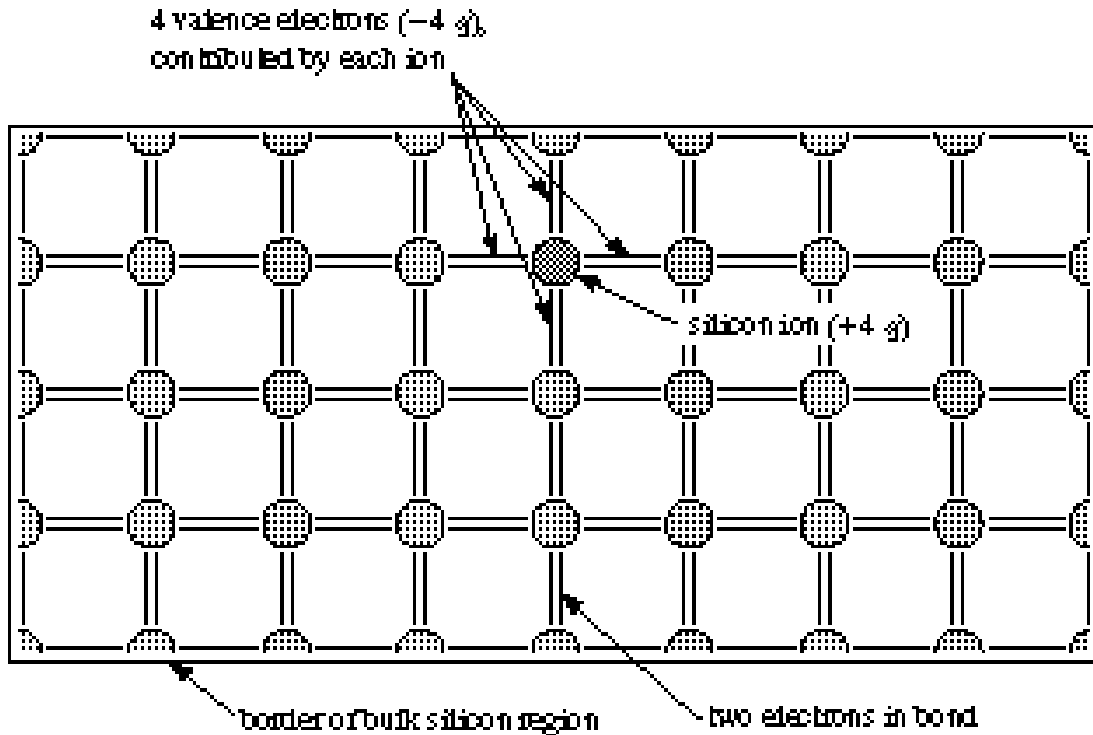
- Electronic structure of silicon atom:
  - 10 core electrons (tightly bound)
  - 4 valence electrons (loosely bound, responsible for most of the chemical properties)
- Other semiconductors:
  - Ge, C (diamond form)
  - GaAs, InP, InGaAs, InGaAsP, GaN, ZnSe, CdTe (on the average, 4 valence electrons per atom)

# Silicon crystal structure



- Diamond lattice: atoms tetrahedrally bonded by sharing valence electrons
  - *covalent bonding*
- Each atom shares 8 electrons
  - *low energy situation*
- Si atomic density :  $5 \times 10^{22} \text{ cm}^{-3}$

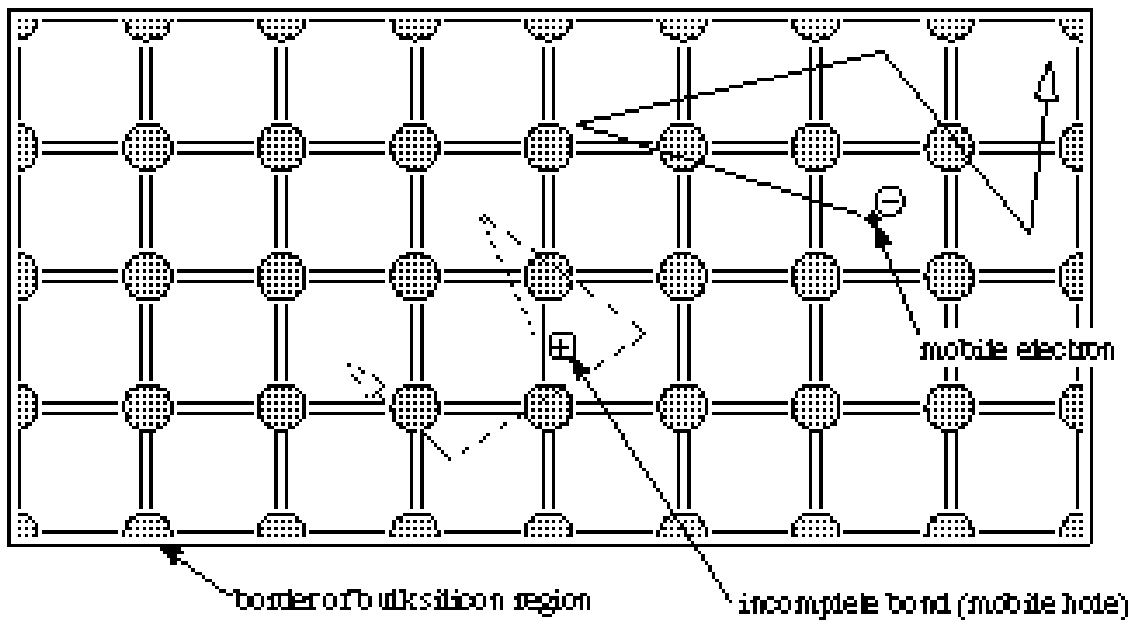
## Simple “flattened” model of Si crystal



At 0K:

- All bonds are satisfied
  - all valence electrons engaged in bonding
- No “free” electrons

## At finite temperature



- Finite thermal energy
- Some bonds are broken
- “free” electrons
  - Mobile negative charge,  $-1.6 \times 10^{-19} \text{ C}$
- “free” holes
  - Mobile positive charge,  $+1.6 \times 10^{-19} \text{ C}$

**Caution: picture is misleading!**

Electrons and holes in semiconductors are “fuzzier”:  
they span many atomic sites

## A few definitions:

- In 6.012, “electron” means free electron
- Not concerned with bonding electrons or core electrons
- Define:
  - $n$  (free) electron concentration [ $\text{cm}^{-3}$ ]
  - $p$  hole concentration [ $\text{cm}^{-3}$ ]

## 2. Generation and Recombination

**GENERATION** = break-up of covalent bond to form electron and hole

- Requires energy from thermal or optical sources (or other external sources)
- **Generation rate:**  $G = G(\text{th}) + G_{\text{opt}} + \dots [\text{cm}^{-3} \cdot \text{s}^{-1}]$
- In general, *atomic density*  $\gg n, p$

$$G \propto f(n, p)$$

- supply of breakable bonds virtually inexhaustible

**RECOMBINATION** = formation of covalent bond by bringing together electron and hole

- Releases energy in thermal or optical form
- **Recombination rate:**  $R = [\text{cm}^{-3} \cdot \text{s}^{-1}]$
- 1 recombination event requires 1 electron + 1 hole

$$R \propto n \cdot p$$

Generation and recombination most likely at surfaces where periodic crystalline structure is broken

### 3. Intrinsic semiconductor

**QUESTION:** In a perfectly pure semiconductor in thermal equilibrium at finite temperature, how many electrons and holes are there?

**THERMAL EQUILIBRIUM =**  
Steady state + absence of external energy sources

## 4. Doping

**Doping** = engineered introduction of foreign atoms to modify semiconductor electrical properties

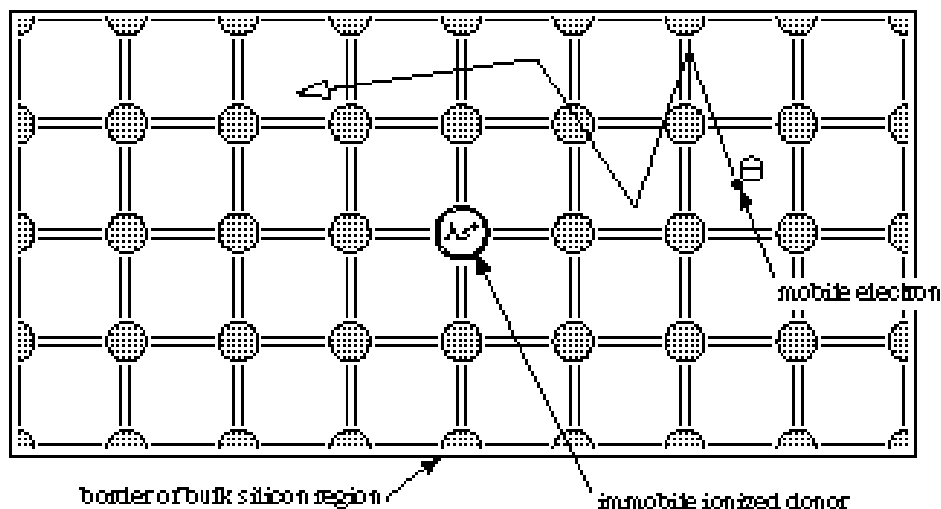
### A. DONORS:

- Introduce *electrons* into the semiconductor (but not holes)
- For Si, group V elements with 5 valence electrons (As, P, Sb)

	IIIA	IVA	VA	VIA	
	<sup>5</sup> B	<sup>6</sup> C	<sup>7</sup> N	<sup>8</sup> O	
	<sup>13</sup> Al	<sup>14</sup> Si	<sup>15</sup> P	<sup>16</sup> S	
IIB	<sup>30</sup> Zn	<sup>31</sup> Ga	<sup>32</sup> Ge	<sup>33</sup> As	<sup>34</sup> Se
	<sup>48</sup> Cd	<sup>49</sup> In	<sup>50</sup> Sn	<sup>51</sup> Sb	<sup>52</sup> Te

## Doping: Donors Contd...

- 4 electrons participate in bonding
- 5<sup>th</sup> electron easy to release
  - at room temperature, each donor releases 1 electron that is available for conduction
- Donor site become positively charged (fixed charge)



Define:

$N_d$  donor concentration [ $\text{cm}^{-3}$ ]

- If  $N_d \ll n_i$ , doping is irrelevant
  - *Intrinsic* semiconductor  $n_o = p_o = n_i$

## Doping: Donors Contd...

- If  $N_d \gg n_i$ , doping controls carrier conc..
  - *Extrinsic* semiconductor

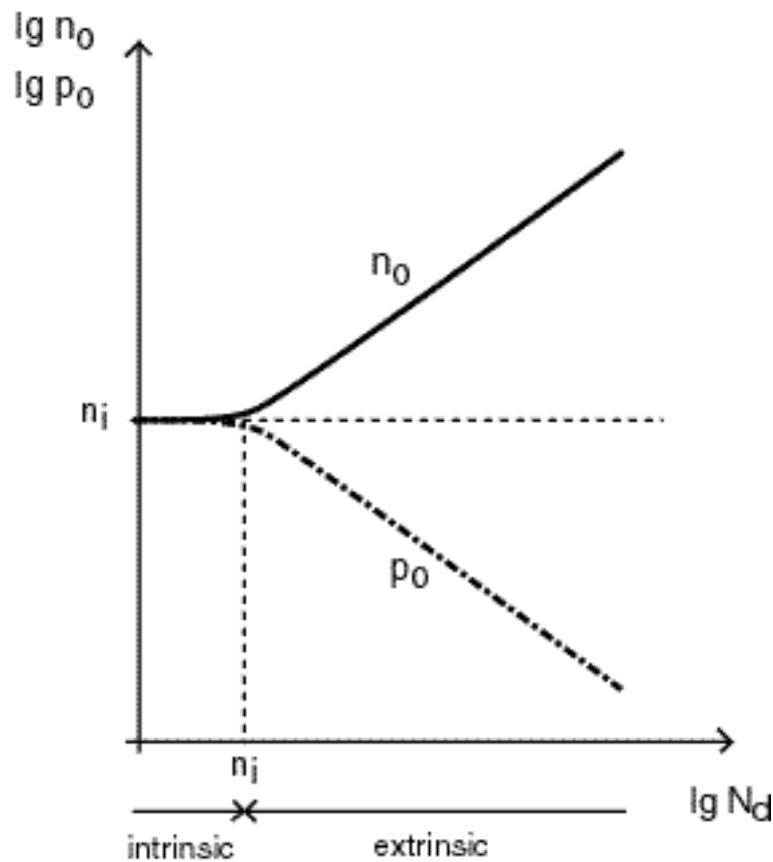
$$n_o = N_d \quad p_o = \frac{n_i^2}{N_d}$$

Note:  $n_o \gg p_o$  : *n-type semiconductor*

### Example:

$$N_d = 10^{17} \text{ cm}^{-3} \quad n_o = 10^{17} \text{ cm}^{-3}, \quad p_o = 10^3 \text{ cm}^{-3}$$

**In general:**  $N_d \quad 10^{15} - 10^{20} \text{ cm}^{-3}$



- **Electrons** = *majority carriers*
- **Holes** = *minority carriers*

# Doping : Acceptors

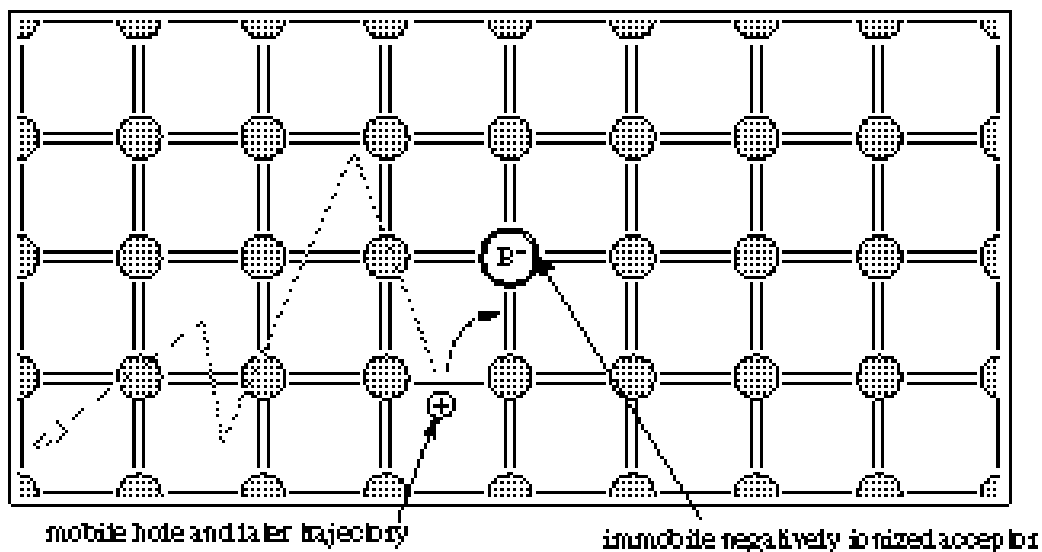
## B. ACCEPTORS:

- Introduce *holes* into the semiconductor (but not electrons)
- For Si, group III elements with 3 valence electrons (B)

	IIIA	IVA	VA	VIA	
	<sup>5</sup> B	<sup>6</sup> C	<sup>7</sup> N	<sup>8</sup> O	
	<sup>13</sup> Al	<sup>14</sup> Si	<sup>15</sup> P	<sup>16</sup> S	
IIB	<sup>30</sup> Zn	<sup>31</sup> Ga	<sup>32</sup> Ge	<sup>33</sup> As	<sup>34</sup> Se
	<sup>48</sup> Cd	<sup>49</sup> In	<sup>50</sup> Sn	<sup>51</sup> Sb	<sup>52</sup> Te

## Doping: Acceptors Contd...

- 3 electrons used in bonding to neighboring Si atoms
- 1 bonding site “unsatisfied” making it easy to “accept” neighboring bonding electron to complete all bonds
  - at room temperature, each acceptor releases 1 hole that is available for conduction
- Acceptor site become negatively charged (fixed charge)



Define:

$N_a$  acceptor concentration [ $\text{cm}^{-3}$ ]

- If  $N_a \ll n_i$ , doping is irrelevant
  - *Intrinsic* semiconductor  $n_o = p_o = n_i$

## Doping: Acceptors Contd...

- If  $N_a \gg n_i$ , doping controls carrier conc.
  - *Extrinsic* semiconductor

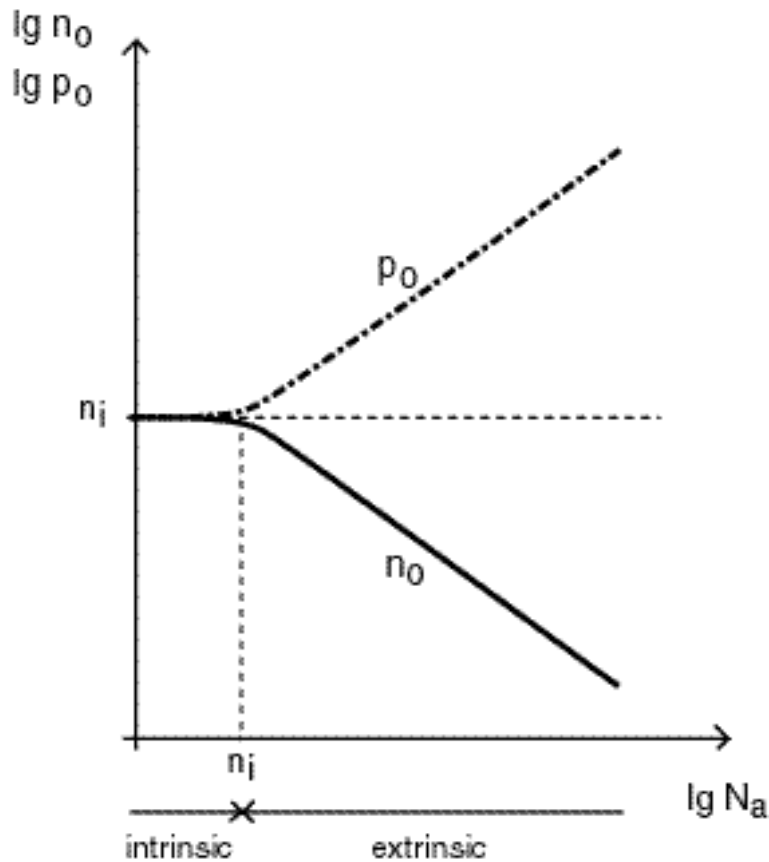
$$p_o = N_a \quad n_o = \frac{n_i^2}{N_a}$$

Note:  $p_o \gg n_o$  : *p-type semiconductor*

### Example:

$$N_a = 10^{17} \text{ cm}^{-3} \quad p_o = 10^{17} \text{ cm}^{-3}, \quad n_o = 10^3 \text{ cm}^{-3}$$

**In general:**  $N_a \quad 10^{15} - 10^{20} \text{ cm}^{-3}$



- **Holes** = *majority carriers*
- **Electrons** = *minority carriers*

## 5. Charge Neutrality

- Every single atom in a semiconductor (doped & undoped) is charge neutral
  - Overall charge neutrality must be satisfied
- In general:

$$= q(p_o - n_o + N_d - N_a)$$

Let us examine this for  $N_d = 10^{17} \text{ cm}^{-3}$ ,  $N_a = 0$

We solved this in an earlier example:

$$n_o = N_d = 10^{17} \text{ cm}^{-3}, \quad p_o = \frac{n_i^2}{N_d} = 10^3 \text{ cm}^{-3}$$

Hence:

**0 !!**

**What is wrong??**

## Charge Neutrality contd...

**Nothing is wrong!**

We just made an approximation when we assumed that

$$n_o = N_d$$

We should really solve the following system of equations  
(for  $N_a=0$ ):

$$p_o - n_o + N_d = 0$$

$$n_o p_o = n_i^2$$

Solution and discussion tomorrow in recitation.

**Error in most practical circumstances too small to matter!**

# Summary

## Why are IC's made out of Silicon?

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- Two types of “carriers” (mobile charge particles):
  - electrons and holes
- Carrier concentrations can be controlled over many orders of magnitude by addition “dopants”
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- Carrier concentrations can be controlled electrostatically
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